

IN THE CLAIMS:

This listing of claims will replace all prior versions, and listings, of claims in the application:

1.-11. (Cancelled)

12. (Previously presented) A lithographic apparatus, comprising:
a radiation system configured to provide a projection beam of radiation;
a support configured to support a patterning device, the patterning device configured to pattern the beam according to a desired pattern;
a substrate table configured to hold a substrate;
a projection system configured to project the patterned beam onto a target portion of the substrate; and
a polarizer device constructed and arranged to polarize said beam of a radiation in a transverse electric polarization direction, said polarizer device comprising a plurality of elongated elements and a thin layer of absorbing material, said thin layer of absorbing material absorbing radiation at a wavelength of said beam of radiation,
wherein said plurality of elongated elements are coated with said thin layer of absorbing material.

13. (Original) A lithographic projection apparatus according to claim 12,
wherein said polarizer device further comprises:
a first layer of material having a first refractive index;
a second layer of material having a second refractive index; and
said plurality of elongated elements are azimuthally and periodically spaced apart, and disposed between said first layer and said second layer, said plurality of elongated elements interact with said beam of radiation to transmit transverse electric polarization of said beam of radiation.

14. (Original) A lithographic projection apparatus according to claim 12,
wherein said polarizer device further comprises:
a substrate material having a first index; and

said plurality of elongated elements are azimuthally oriented and coupled with said substrate material, said elongated elements having a second refractive index, said plurality of elongated elements are periodically spaced apart to form a plurality of gaps such that said polarizer device interacts with the beam of radiation comprising first and second polarizations to reflect substantially all of the radiation of the first polarization and transmit substantially all of the radiation of the second polarization.

15. (Original) A lithographic projection apparatus according to claim 14,
wherein said thin layer of absorbing material is selected such that a portion of reflected radiation of the first polarization transformed into a secondary radiation of a second polarization is substantially absorbed by said thin layer of absorbing material.
16. (Original) A lithographic projection apparatus according to claim 14,
wherein the radiation of the second polarization is minimally absorbed by said thin layer of absorbing material.
17. (Original) A lithographic projection apparatus according to claim 14,
wherein said thin layer of absorbing material substantially eliminates polarization flare in the transmitted radiation of a second polarization.
18. (Original) A lithographic projection apparatus according to claim 14,
wherein the second polarization is a transverse electric polarization.
19. (Original) A lithographic projection apparatus according to claim 12,
wherein said thin layer of absorbing material is selected from the group: Al_2O_3 and anodic oxidized aluminum.
20. (Original) A lithographic projection apparatus according to claim 12,
wherein a wavelength range of said radiation beam is in the ultraviolet spectrum.
21. (Original) A lithographic projection apparatus according to claim 20,
wherein said wavelength range is between 365 nm and 126 nm.
22. (Previously presented) A lithographic projection apparatus according to claim 20,

wherein said wavelength range is in the extreme ultraviolet.

23.- 32. (Cancelled)